

**ABSTRACT OF THE DISCLOSURE**

The invention provides method of etching and cleaning objects contained in a vessel, including: etching the objects by providing etching solution into the vessel; exiting  
5 the etching solution from the vessel by providing pressurized gas into the vessel; cleaning the objects by providing cleaning solution into the vessel; and draining the cleaning solution from the vessel. By exiting the etching with pressurized gas such as nitrogen gas, there is no density difference of the etching solution through out the objects, leading to uniform etching of the objects.